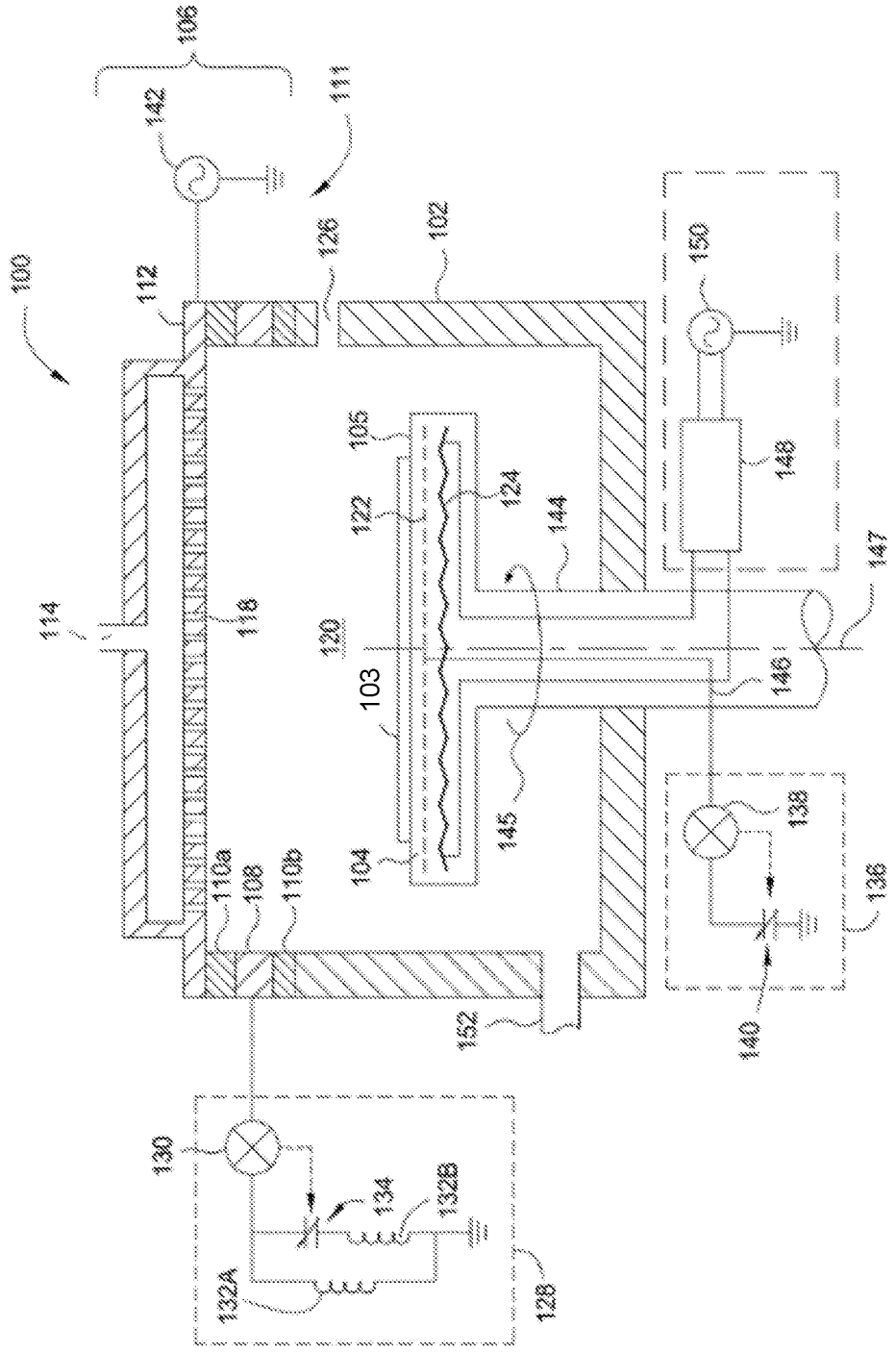

106
142
111
126
102
100
112
150
105
148
122
124
144
147
114
116
120
103
146
145
138
104
110a
108
110b
136
152
140
130
134
132B
132A
128

FIG. 1

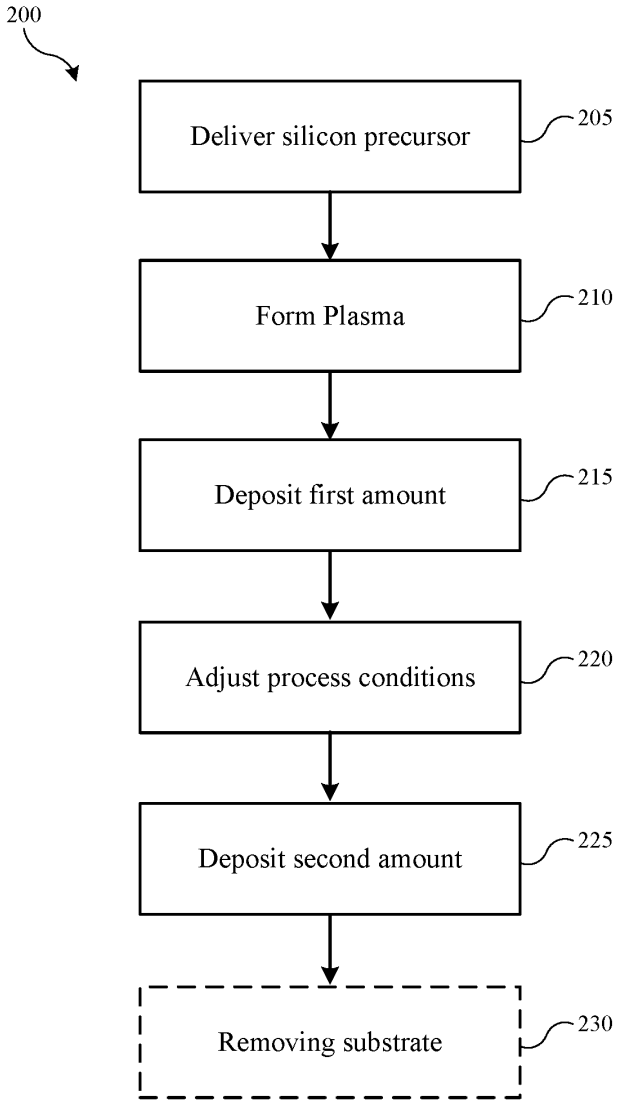

200
Deliver silicon precursor
205
Form Plasma
210
Deposit first amount
215
Adjust process conditions
220
Deposit second amount
225
Removing substrate
230

FIG. 2

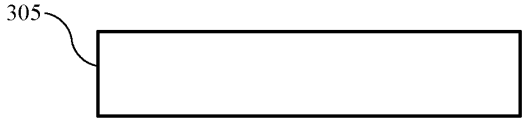


FIG. 3A

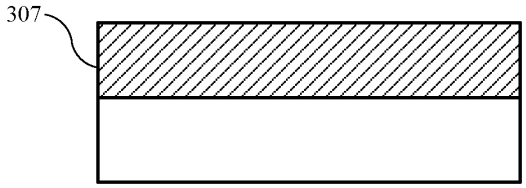


FIG. 3B

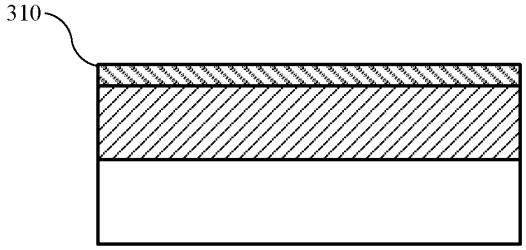


FIG. 3C